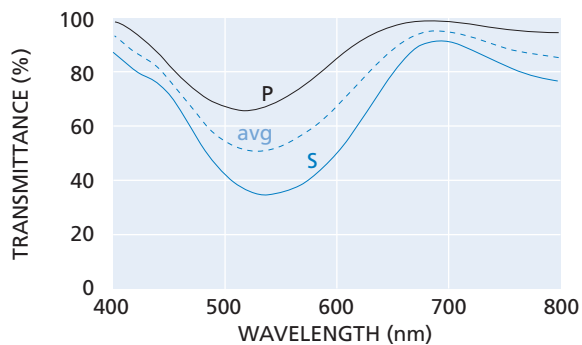




High Energy Ultra Thin Beamsplitters

All dielectric, nonabsorbing coating and fused silica substrate make this an ideal beamsplitter for high energy beamsplitting. Use this beamsplitter when you need to minimize beam displacement.

- User specified reflectance from 1 percent to 99.5 percent
- User specified CWL from 244 nm to 2100 nm
- The standard 1.25" OD fits into a 1.25" Series 200 mount



Ultra thin beamsplitter optimized for 50% at 532nm

SPECIFICATIONS: High Energy Ultra Thin Beamsplitters

Optical Material	UV-grade fused silica
Beam Displacement	100 μ m
Surface Figure	2 λ at 633 nm before coating
Surface Quality	10-5 scratch and dig
Angle of Incidence	45°
Wedge	≤5 arc min
Housing Material	Black-anodized aluminum
Housing Diameter	31.8 mm
Housing Thickness	6.35 mm
Substrate Thickness	0.30 mm
Coating Technology	Electron beam multilayer dielectric
Adhesion and Durability	Per MIL-C-675C.
Transmitted	Insoluble in lab solvents.
Wavefront Error	$\lambda/10$ at 633 nm
$R_s - R_p , T_s - T_p$	<5%
Clear Aperture	≥85% of central diameter
Damage Threshold	
Pulsed	10 J/cm ² , 20 nsec, 20 Hz @ 1064 nm
cw	1 MW/cm ² @ 1064 nm

Build Your Own

Product Code

UT

Center Wavelength nm

257	355	488/515	578	780	900	1064	1550
266	400	532	633	800	1053	1319	2100

Reflectance %

10 ± 4.0	25 ± 5.0	33 ± 5.0	50 ± 5.0	67 ± 5.0	75 ± 5.0	90 ± 3.0	98 ± 1.0
20 ± 5.0	30 ± 5.0	40 ± 5.0	60 ± 5.0	70 ± 5.0	80 ± 5.0	95 ± 2.0	99 ± 0.5

Angle of Incidence in degrees with Polarization

45P	45S	45UNP
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